	L #	Hits	Search Text	DBs
1	L1	841745	magnetorestrictive or magneto adj restrictive or magnetic	EPO; JPO; DERWENT; IBM_TDB
2	L2	1142076	sensor or sensing	EPO; JPO; DERWENT; IBM_TDB
3	L3	131189	polish$8 or cmp	EPO; JPO; DERWENT; IBM_TDB
4	L4	262	1 and 2 and 3	EPO; JPO; DERWENT; IBM_TDB
5	L5	188110	(magnetic or bias) near3 (layer or film or material)	EPO; JPO; DERWENT; IBM_TDB
6	L6	90	4 and 5	EPO; JPO; DERWENT; IBM_TDB
7	L7	207787	resist or photoresist	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
8	L8	14	6 and 7	EPO; JPO; DERWENT; IBM_TDB
9	L9	715	3 near5 2	EPO; JPO; DERWENT; IBM_TDB
10	L10	49	1 and 9	EPO; JPO; DERWENT; IBM_TDB
11	L11	45	10 not 8	EPO; JPO; DERWENT; IBM_TDB
12	L12	12155	liftoff or lift$4 adj off	EPO; JPO; DERWENT; IBM_TDB
13	L13	48	1 and 2 and 12 and 5	EPO; JPO; DERWENT; IBM_TDB
14	L14	45	13 not (8 or 10)	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
15	L15	48838	trench	EPO; JPO; DERWENT; IBM_TDB
16	L16	118	5 near5 15	EPO; JPO; DERWENT; IBM_TDB
17	L17	5	1 and 16 and 2	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
1	L1	75032	magnetoresistive or mr or magneto adj resistive	US-PGPUB; USPAT
2	L2	592894	electrode	US-PGPUB; USPAT
3	L3	268057	"sio.sub.2" or silicon adj dioxide	US-PGPUB; USPAT
4	L4	394859	resist or photoresist	US-PGPUB; USPAT
5	L5	173195	seed	US-PGPUB; USPAT
6	L6	12293	sio2	US-PGPUB; USPAT
7	L7	50540	ion adj etch$4	US-PGPUB; USPAT
8	L8	729397	sensor	US-PGPUB; USPAT
9	L9	222458	cmp or polish$8	US-PGPUB; USPAT
10	L10	16	1 and 2 and (3 or 6) and 4 and 5 and 7 and 8 and 9	US-PGPUB; USPAT
11	L11	5038	(current adj2 perpendicular adj2 plane) or cpp	US-PGPUB; USPAT
12	L12	58728	reactive adj ion adj etch$4 or rie	US-PGPUB; USPAT
13	L13	1512	hard adj bias	US-PGPUB; USPAT
14	L14	30	1 and 5 and 13 and 9 and 12 and 11	US-PGPUB; USPAT
15	L16	17	1 and 4 and 5 and 13 and 9 and 12 and 11 and (3 or 6)	US-PGPUB; USPAT